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(12) **United States Design Patent**
Gopalraja et al.

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(54) **SPUTTERING CHAMBER COIL**

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U.S Patent Application Serial No. 08/559,345 filed Nov. 15, 1995 (Atty Dkt 938.X1/4479).
U.S. Patent Application Serial No. 08/730,722 filed Oct. 8, 1996 (Atty Dkt 1207/4784).
U.S. Patent Application Serial No. 09/049,276 Mar. 27, 1998 (Atty Dkt 938.D2/5703).
U.S. Patent Application Serial No. 09/049,839 Mar. 27, 1998 (Atty Dkt 938.D1/5702).
Applied Materials, Inc., Exhibit A, Dated Prior to Jul. 13, 1998, the filing date of the present application.(Exhibit A is a drawing of a prior art coil design which is prior to the design of the present application.).

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(**) **Term:** **14 Years**

(21) **Appl. No.:** **29/090,618**

(22) **Filed:** **Jul. 13, 1998**

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(52) **U.S. Cl.** **D15/144.2**

(58) **Field of Search** D15/199, 144.2;
204/298, 192.12, 192.13, 298.03, 298.19,
298.2, 298.01, 298.02, 298.05; 315/111.21,
111.41, 111.51, 111.81

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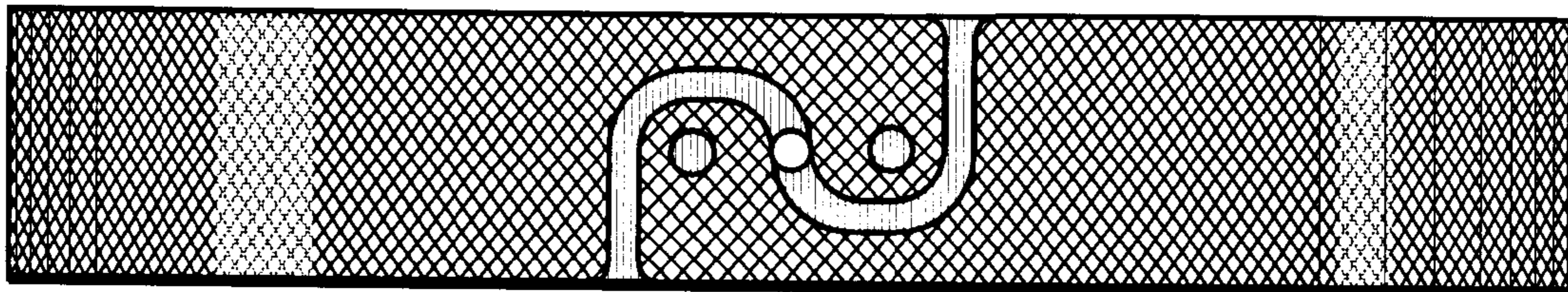
(57) **CLAIM**

The design for sputtering chamber coil, as shown and described.

DESCRIPTION

FIG. 1 is a front elevational view;
FIG. 2 is a top view;
FIG. 3 is a right side elevational view;
FIG. 4 is a bottom view; and,
FIG. 5 is a rear elevational view of our sputtering chamber coil.
The left side elevation view (not shown) is the same as the right side elevational view (FIG. 3) because of coil symmetry.

1 Claim, 2 Drawing Sheets



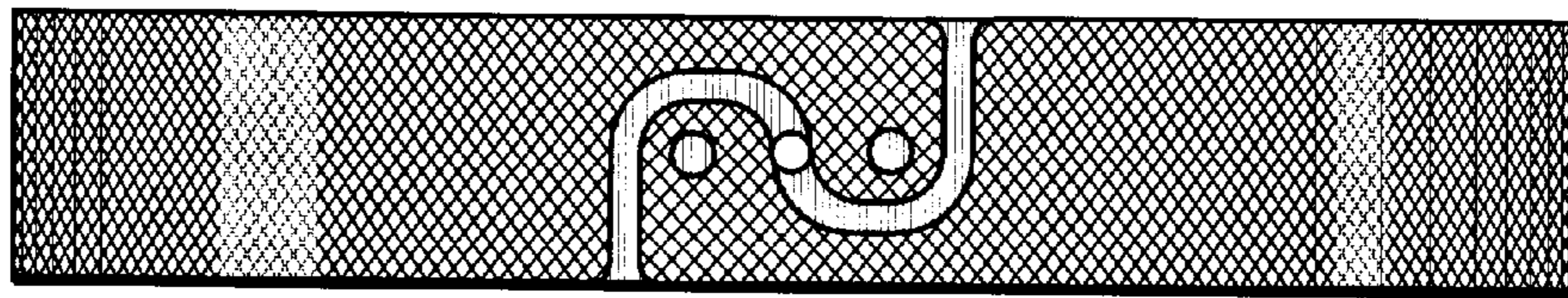


Fig. 1

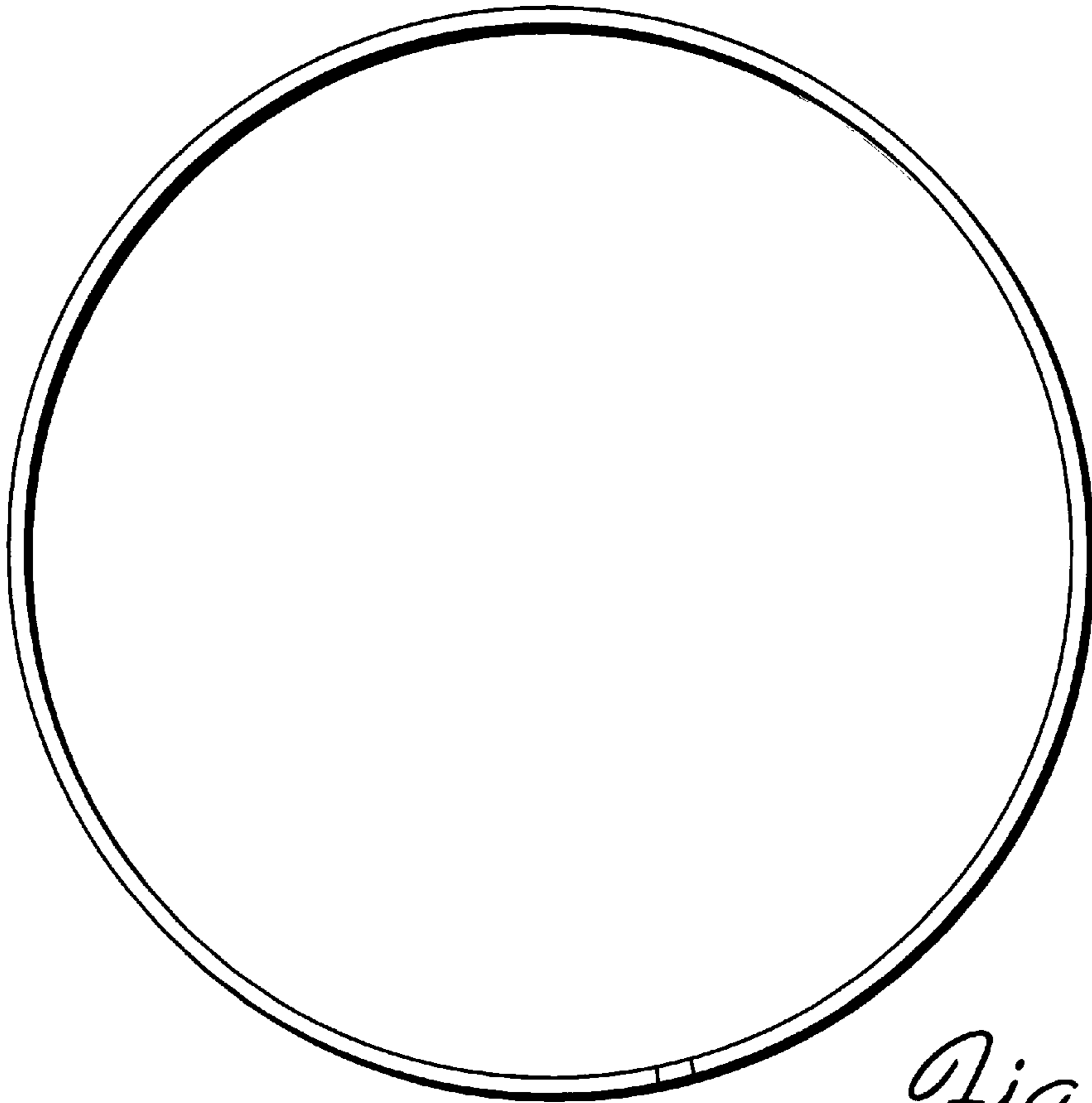


Fig. 2

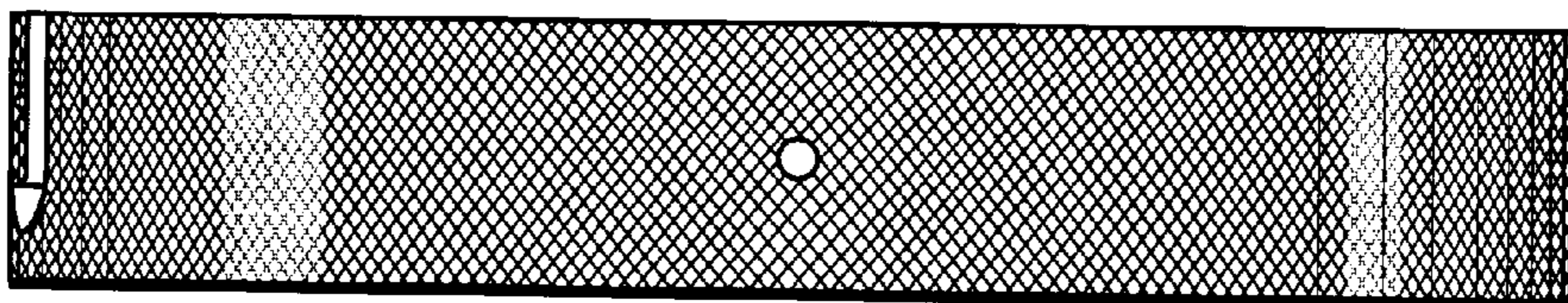


Fig. 3

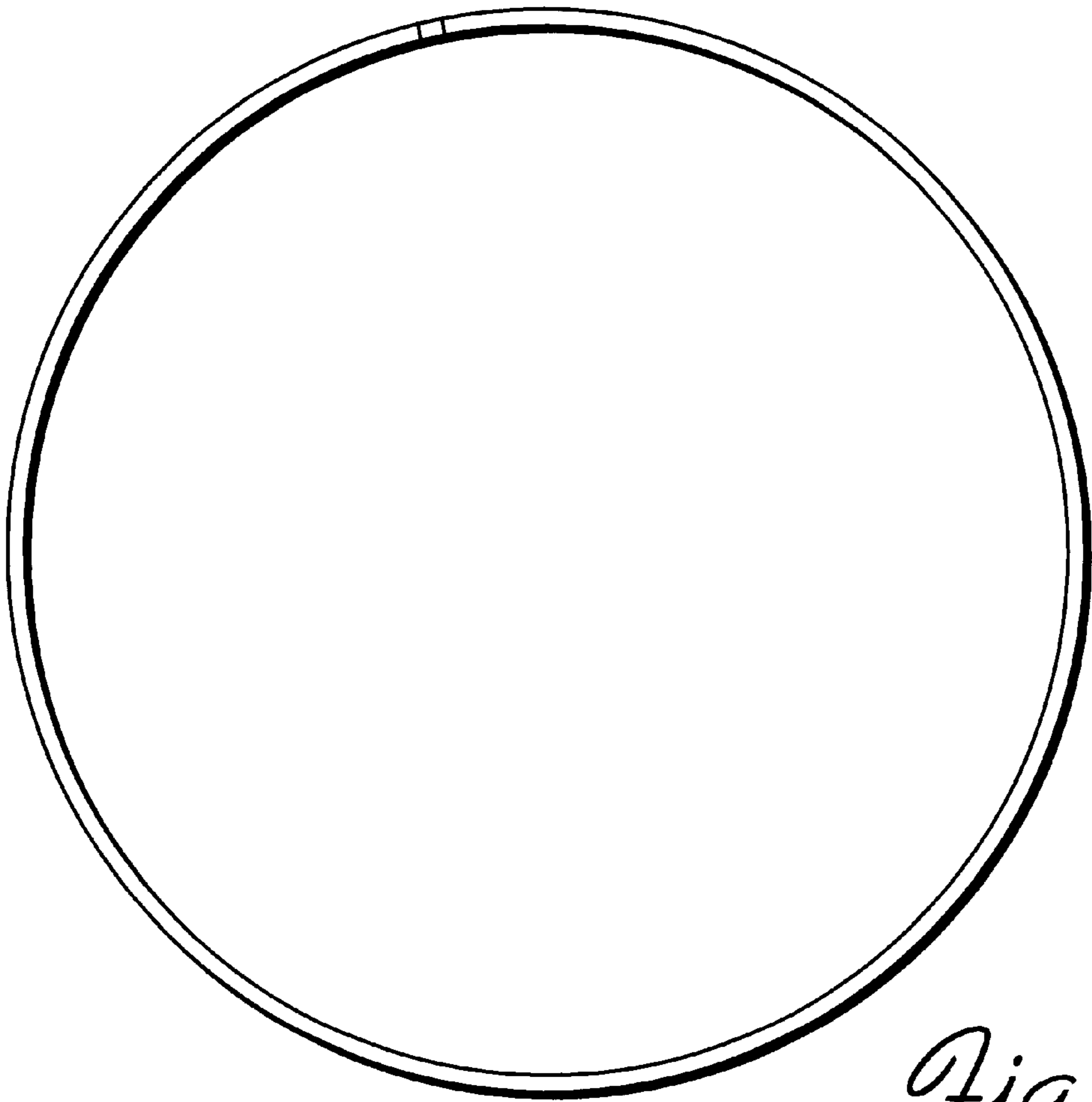


Fig. 4

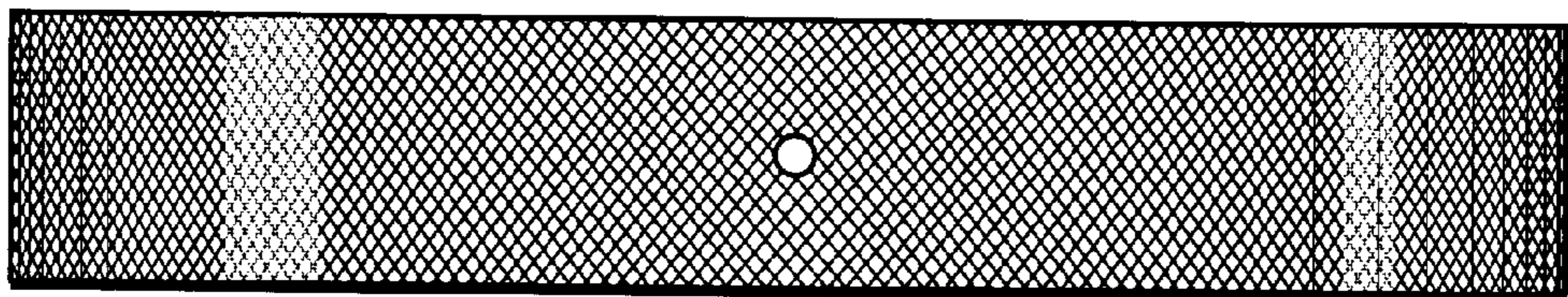


Fig. 5